

Session	Speakers	Company	Paper Title	O/P
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Oral Presentation Slots are now full!

Additional Poster Papers to be Announced!

Post-deadline poster papers accepted until May 23, 2017.

Session 1: Keynote	P1	Obert Wood	GlobalFoundries	EUV: current status & remaining challenges	O
	P2	Hakaru Mizoguchi	Gigaphoton	High Power HVM LPP-EUV Source with Long Collector Mirror Lifetime	O
	P3	Britt Turkott	Intel	Challenges of EUV Lithography for HVM	O
	P4	Margaret Murnane	Univ. of Colorado	Tabletop Coherent EUV Sources and Applications: Full Field Sub-Wavelength Imaging at 13.5nm and Materials Metrology	O
	P5	Igor Fomenkov	Cymer	EUV Lithography: Progress in LPP Source Power Scaling and Availability	O

Session 2: Source	P11	Akira Endo	HiLASE	kW-class picosecond thin-disk pre-pulse laser Perla for efficient EUV generation	O
	P12	Yasui Koji	Mitsubishi	Scalability of CO ₂ amplifiers to generate stable > 500W extreme ultraviolet (EUV) beams	O
	P13	Howard Scott	LLNL	Simulating EUV Production - an Overview of the Underpinnings	O
	P14	Oscar Versolato	ARCNL	Short-pulsed Nd:YAG laser interaction with tin micro-droplets	O
	P15	Erik Hosler	GlobalFoundries	Next Generation Source Power Requirements: What will we need at the 3 nm node and beyond?	O

P16	Filippos Toufexis	Stanford	A Compact Linac-Driven EUV Light Source utilizing a Short-Period Microwave-Driven Undulator	O
P17	Michael Feser	Lyncean	Concept for 1kW EUV Source for Lithography Based on FEL Emission in Compact Storage Ring	O
P18	Hiroshi Kawata	KEK	Challenges to realize the EUV-FEL high power light source - Present status on the EUV-FEL R&D activities -	O

Session 3: Optics
and Optics
Contamination

			EUV optics life time research, past, present and future	
P21	Norbert Bowerings	TNO		O
P22	Jan van Schoot	ASML	The future of EUV lithography: enabling Moore's law in the next decade	O
P23	Jack Liddle	Zeiss	Latest developments in EUV optics	O
P24	Ladislav Pina	RITE	EUV/SXR Optics and Metrology Development at RITE	O
P25	Takeo Watanabe	Univ. of Hyogo	Large Collector Mirror Reflectometer for the High Power EUV Light Source Achievement	P

Session 4: Mask

P31	YoungWoong Kim	Hanyang	Improved inspection ability of Coherent Scattering Microscopy by applying Ptychography	O
P32	Patrick Helfenstein	PSI	RESCAN - A standalone tool for EUV mask defect inspection	O
P33	Bryan Kasprowicz	Photronics	Extreme Ultraviolet Mask Manufacturing: Challenges and Opportunities (Tentative Title)	O
P34	Takeo Watanabe	Univ. of Hyogo	New SUBARU EUVL R&D Activities and EUV Mask Defect Inspection	O
P35	Aamod Shankar	LBL	Measuring aberrations with mask roughness	P

P36	Yow-Gwo Wang	LBL	Impact of tool design on defect detection sensitivity for EUV actinic blank inspection.	P
P37	Stuart Sherwin	LBL	Rigorous 3D electromagnetic simulation of ultrahigh efficiency EUV contact-hole printing with Chromeless phase shift mask	O
P38	Marcus Benk	LBL	Anamorphic Imaging: Emulating Future Nodes of EUV Lithography on the SHARP Microscope	O
P39	Adrian Devasahayam	Veeco	Reduction of Large Killer Defects in EUV Mask Blanks	O
P40	Xiangzhao Wang	SIOM	Variable Separation Method for Three-dimensional EUVL mask diffraction simulation	P

Session 5: Resist and Patterning

P41	Greg Denbeaux	UAlbany	Reactivity of Metal Oxalate EUV Resists as a Function of the Central Metal	O
P42	Alex Hexemer	LBL	Towards Real-Time Analysis of Morphologies using Scattering	O
P43	Yoshi Hishiro	JSR	Novel EUV resist development for sub-7 nm node	O
P44	Sonia Ortega	ARCNL	Extreme ultraviolet induced chemical reactions in photoresists and model systems	O
P45	Frank Ogletree	LBL	Fundamentals of X-Ray Excitation and Relaxation in EUV Resists (Tentative Title)	O
P46	Seiichi Tagawa	Osaka	Fundamental aspects of PSCAR breaking RLS trade-off and photon shot noise comparing with CAR and non-CAR	O
P47	Greg McIntyre	IMEC	EUV developments at imec	O
P48	Dan Slaughter	LBL	Low energy electron attachment induced chemistry	O
P50	Jason Stowers	Inpria	Metal Oxide Photoresists: Breaking Paradigms in EUV Lithography	O
P51	Fallica Roberto Alfio	PSI	Estimation of lithographically-relevant secondary electron blur	P

P52 Takeo Watanabe	Univ. of Hyogo	EUV Lithography Research and Development Activities at University of Hyogo	P
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P70 Vivek Bakshi	EUV Litho	Meeting Summary
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